

PREPARATION METHOD FOR SEMICONDUCTOR STRUCTURE AND SEMICONDUCTOR STRUCTURE

ABSTRACT

A preparation method for a semiconductor structure and a semiconductor structure are provided. Herein, the preparation method comprises: providing a structure to be processed, wherein the structure to be processed comprises a substrate, and an etching target layer, a bottom mask layer and a first mask layer stacked on the substrate; patterning the first mask layer to form a first pattern, the first pattern exposing parts of the bottom mask layer; forming spacers with vertical sidewall morphology on sidewalls of the first mask layer; removing the first mask layer; filling a gap between the spacers with a filling layer, in which a material of the spacers to a material of the filling layer has a high etching selectivity ratio; and removing the spacers.

[Fig. 1]